

Fabrication of Ordered Cu_2O Quantum Dot Arrays on SrTiO_3 (100)



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Presentation Outline

- **Introduction**

Why we are interested in $\text{Cu}_2\text{O}/\text{SrTiO}_3$.
Why directed self-assembly using FIB.

- **Experiment**

Experiment setup
Experiment procedures

- **Results**

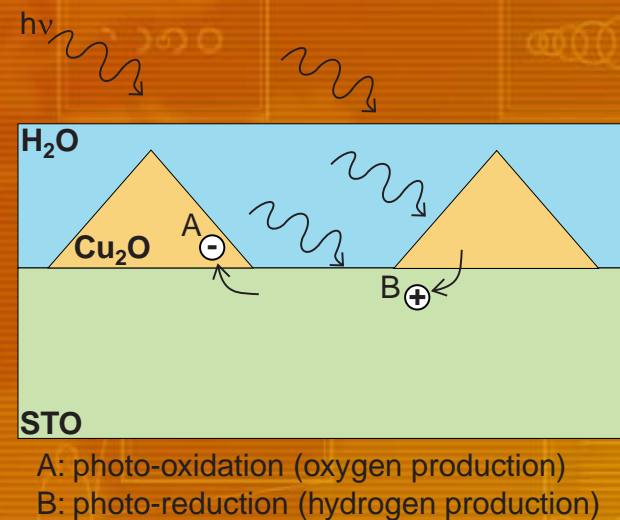
- **Discussions**



Introduction

Why we are interested in $\text{Cu}_2\text{O}/\text{SrTiO}_3$

- Photocatalytic decomposition of water on Cu_2O interface under visible light irradiation¹.
 - Produce hydrogen for fuel cells
 - High density QD array for maximum device efficiency
- Quantum dots – 0 D, size-dependent optical and electrical properties - new applications
 - Cu_2O QDs are expected to exhibit spatially confined exciton states - good candidate to observe Bose-Einstein condensation



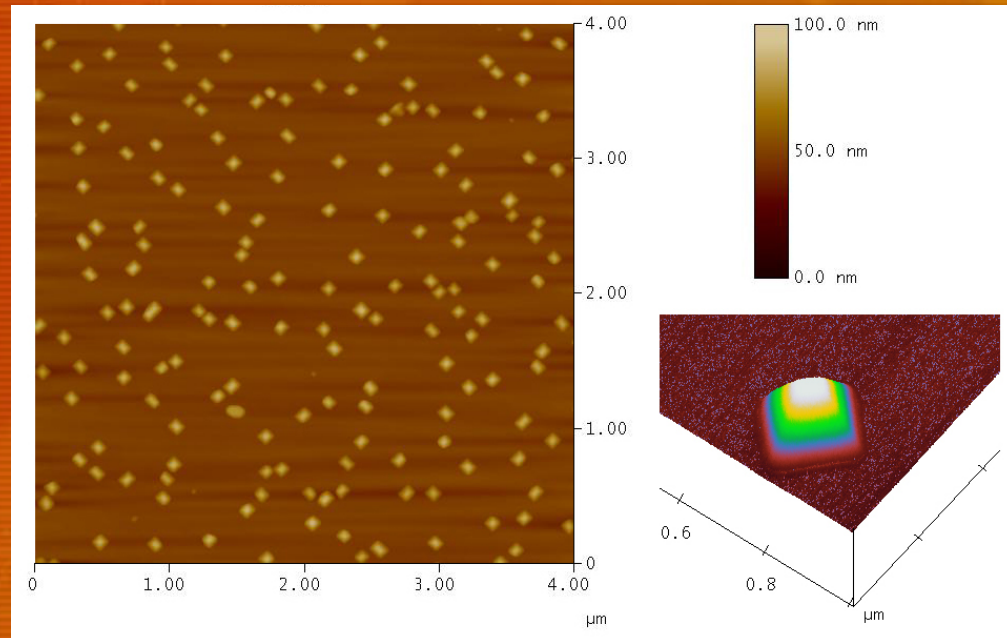
1. M. Hara, T. Kondo, M. Komoda, S. Ikeda, K. Shinohara, A. Tanaka, J. N. Kondo, and K. Domen, *Chem. Commun.* 357 (1998).



Introduction

Why we are interested in directed self-assembly of QDs.

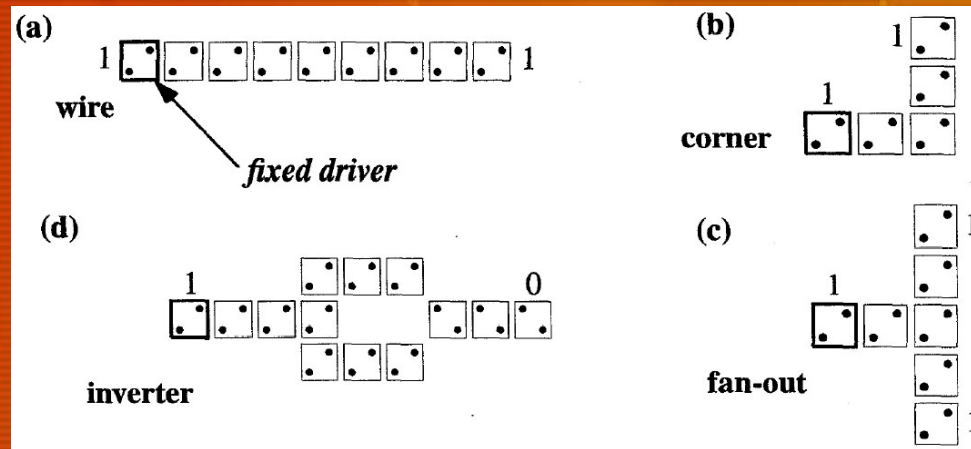
- MBE growth of semiconductor QDs for V, III-V, II-VI.
Oxygen plasma-assisted MBE growth of metal oxide QDs (e.g. $\text{Cu}_2\text{O}/\text{SrTiO}_3$)
 - Self-assemble on lattice mismatched strain system
 - Quasirandom on planar substrate.



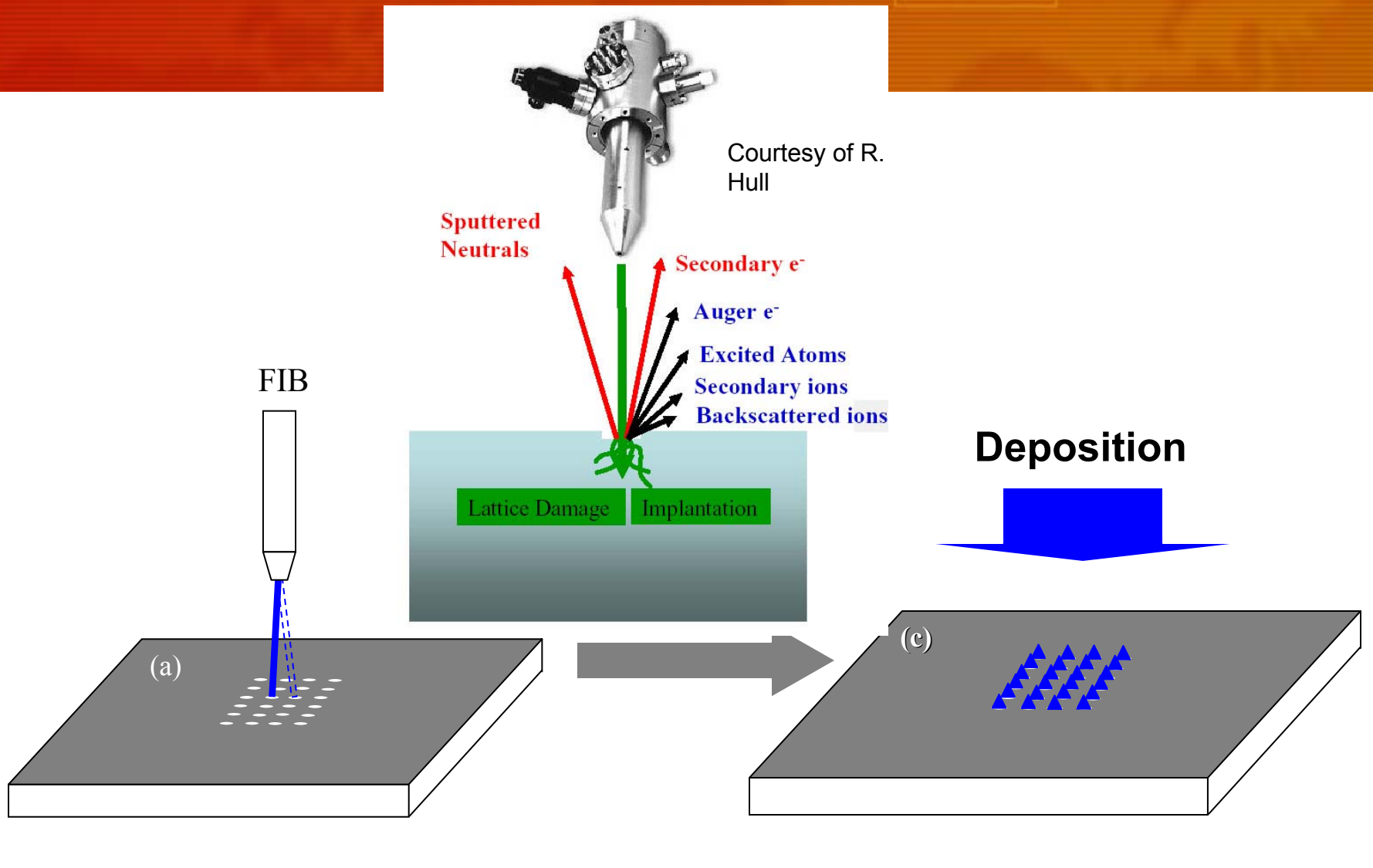
Introduction

Why we are interested in directed self-assembly of QDs.

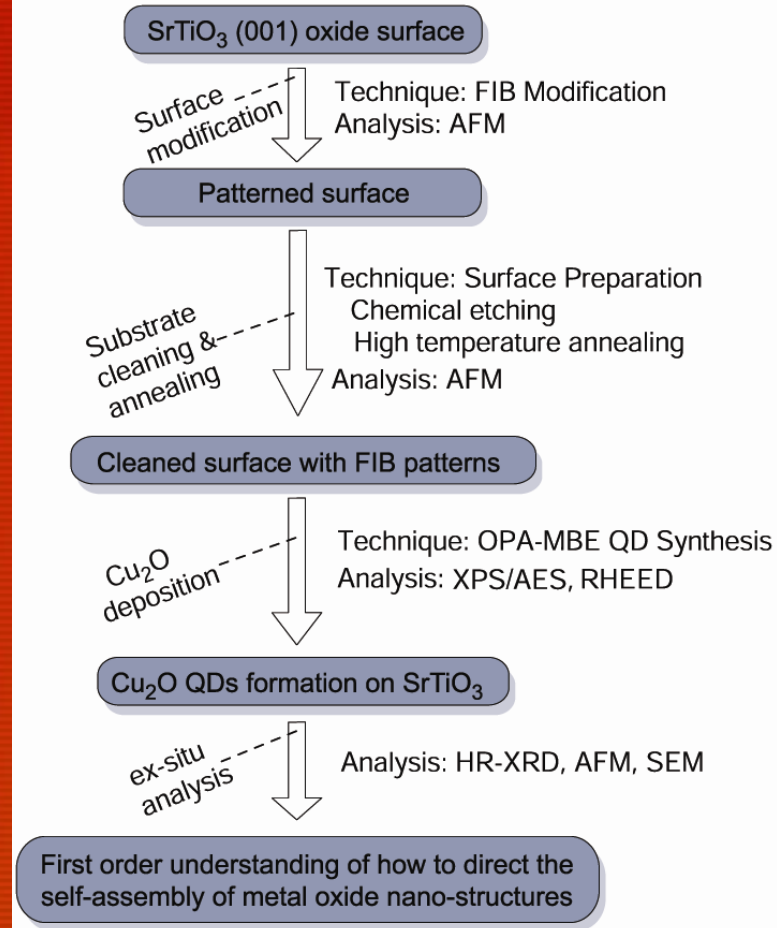
- New nanodevices and new applications
Size and location control - reproducibility
Ability to join the dots into complex assemblies creates many scientific opportunities.
 - Quantum cellular automata²
 - Quantum dot lasers



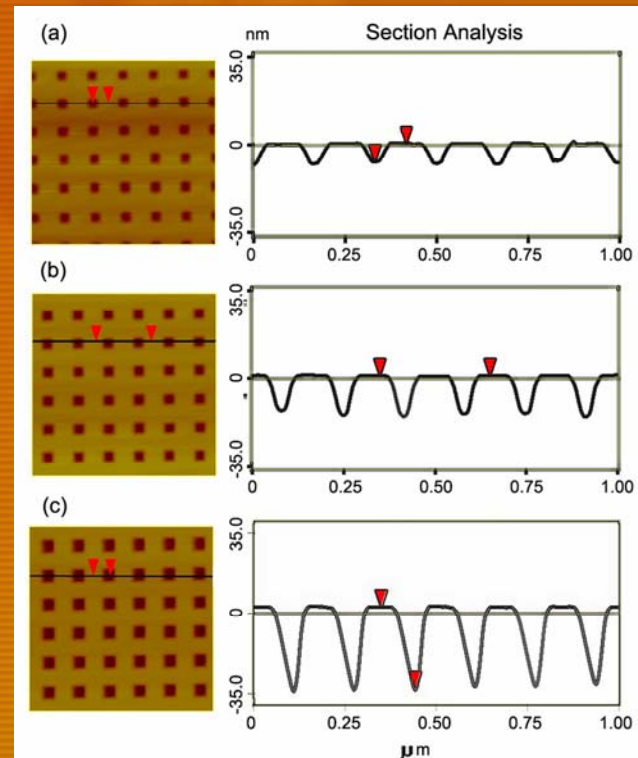
Experiment expectations



Experiment



Experiment steps



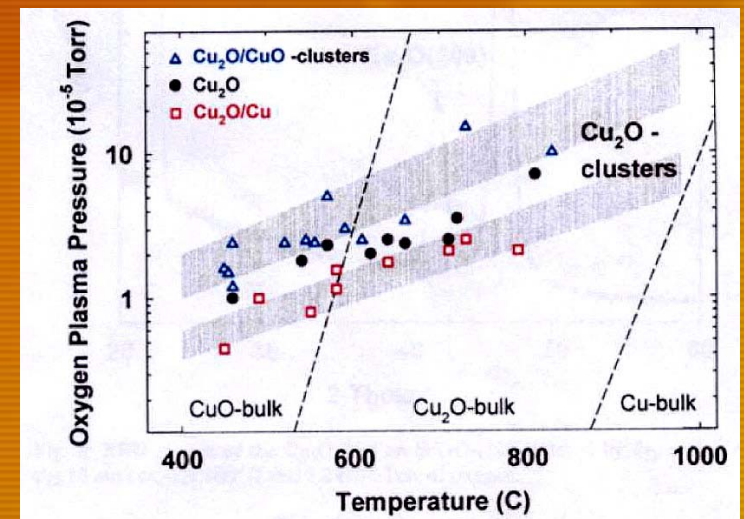
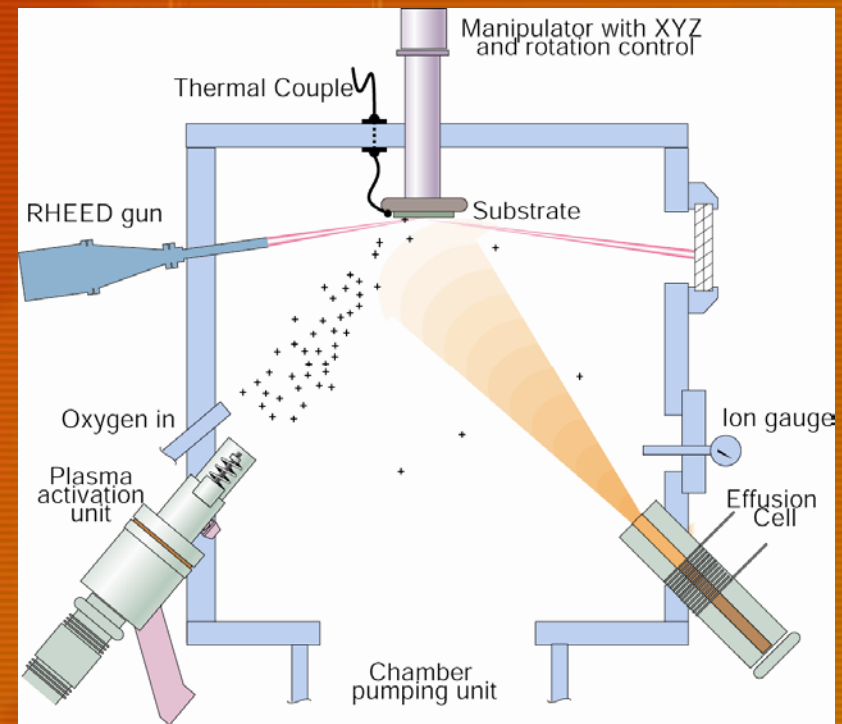
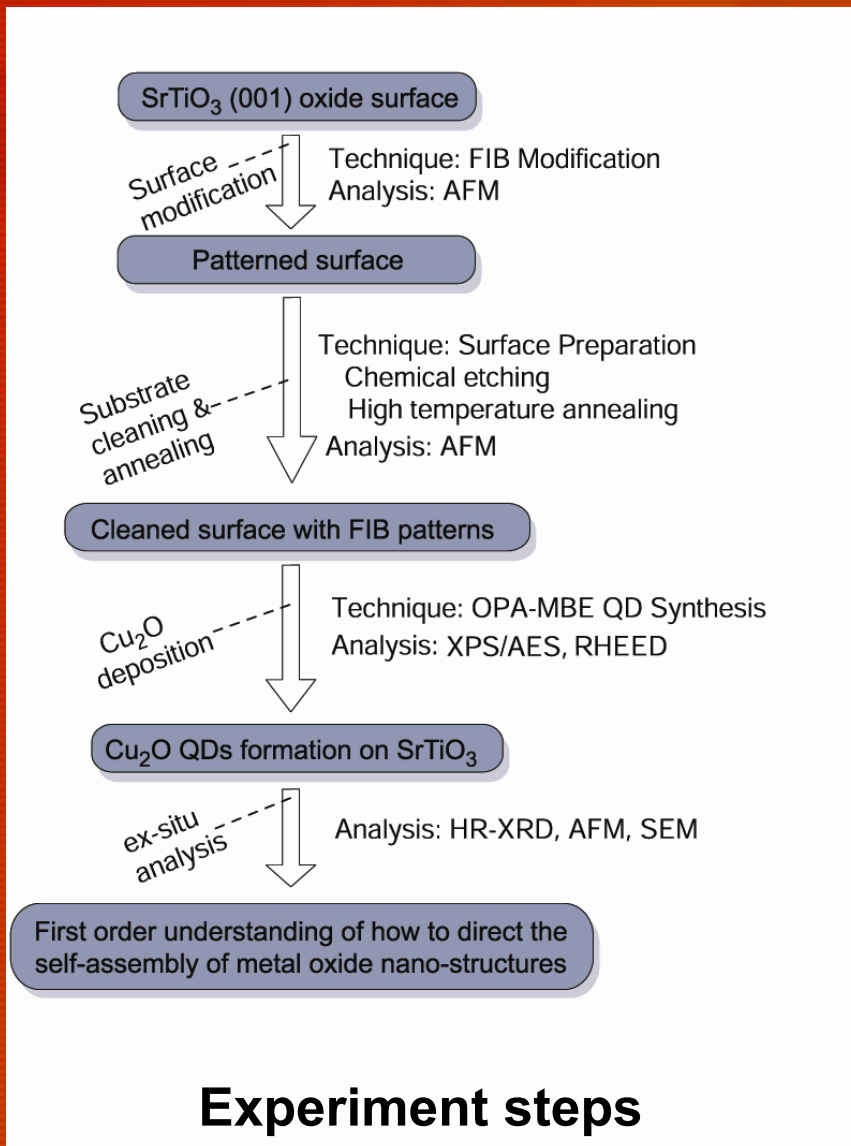
167 nm
5 scans
625x5

167nm
10,

167nm
50

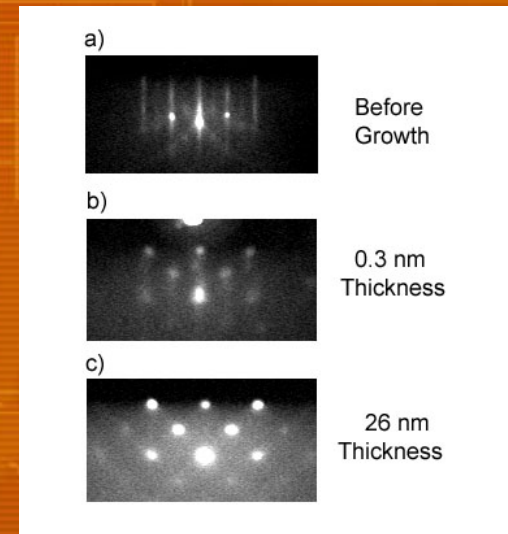
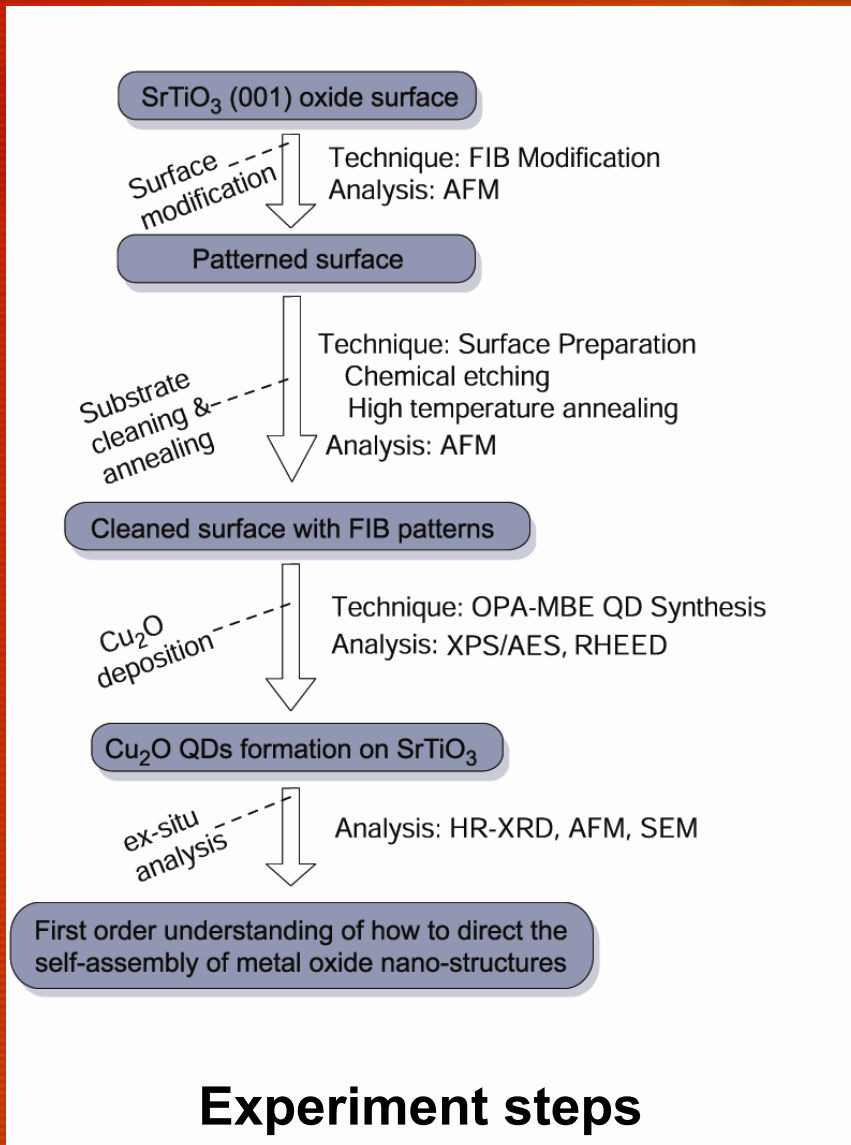


Experiment

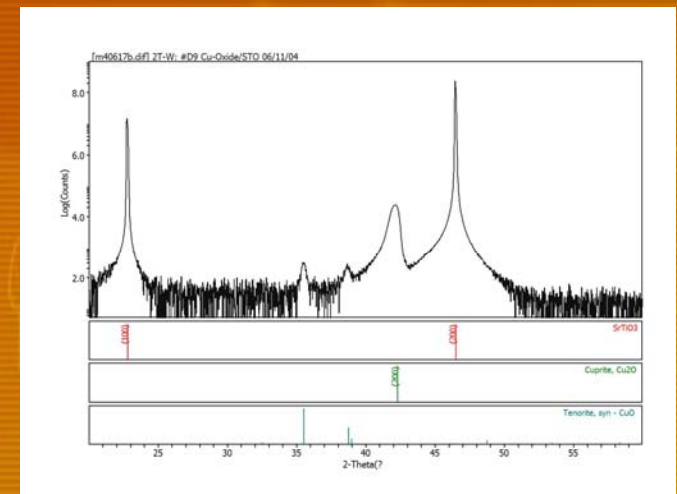


As determined by XPS & AES³

Experiment



**V-W growth
Without wetting**



**HRXRD – Epitaxial
Cu₂O (100) // SrTiO₃ (100)**



Results:

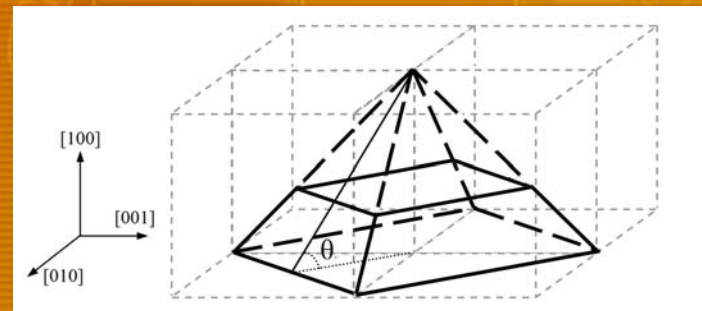
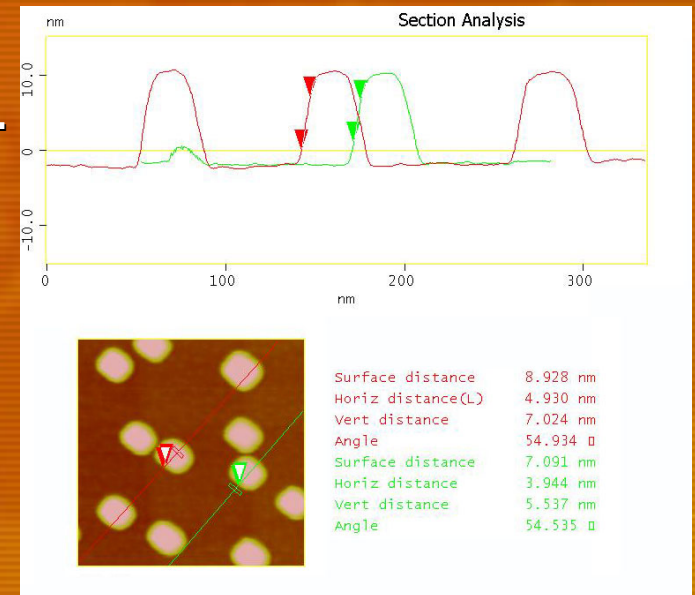
Non-patterned region (Flat SrTiO₃ surface)

- **Shape and size of Cu₂O QDs**
 - Weak dependence on thickness init.
 - Truncated pyramidal crystals
 - {111} side walls with (100) flat tops

Reproducible, stable, epitaxial

- **Density of Cu₂O QDs**
 - Strong dependence on T
 - Fixed T, close to linear with thickness before coalescence.

To fit the pattern, need to adjust density



Results:

Patterned regions : Microscale

- **Best result**
 - One FIB pit – 1-4 nanodot.
 - no islands formed elsewhere

Process conditions:

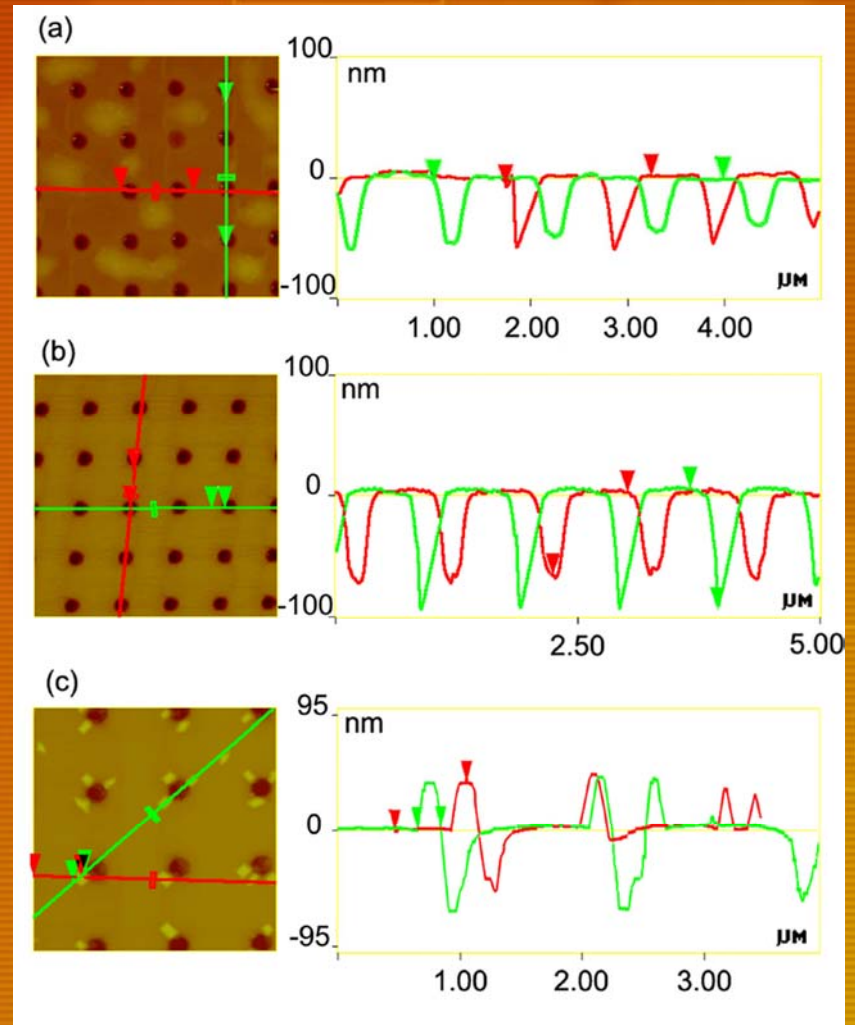
1 μm spacing

$T = 725^\circ\text{C}$

Thickness: 7 \AA

Directions:

1. Reproducibility
2. Higher integration
3. Less surface damage



Ga ion density $5.6 \times 10^{18} \text{ ions/cm}^2$

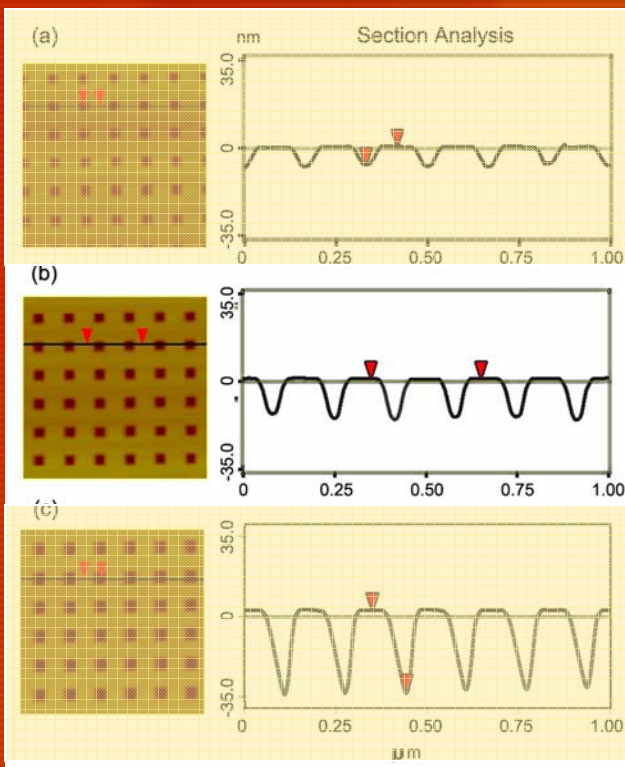
4.4×10^8 Ga ions on each dot



Results:

Patterned regions : Nanoscale

- **Best result**
 - One FIB pit – one nanodot.
 - Few islands formed elsewhere
 - Larger size, lower height

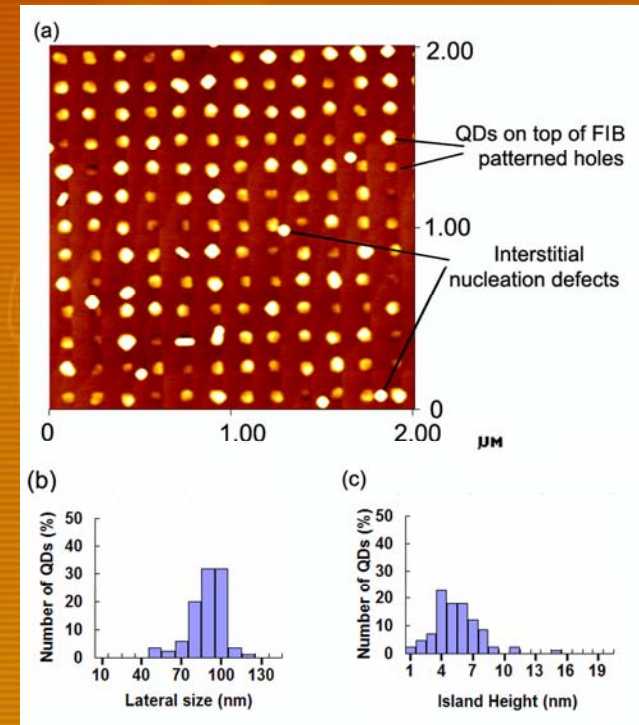


Process conditions:

b) region

T = 700°C

Thickness: 7 Å



Results:

Patterned regions

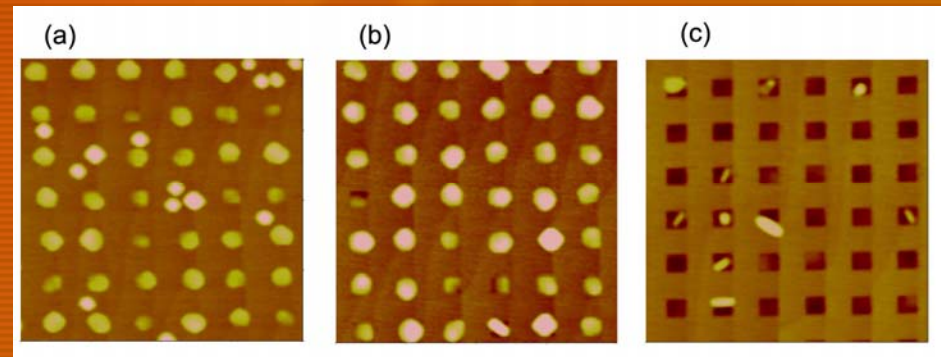
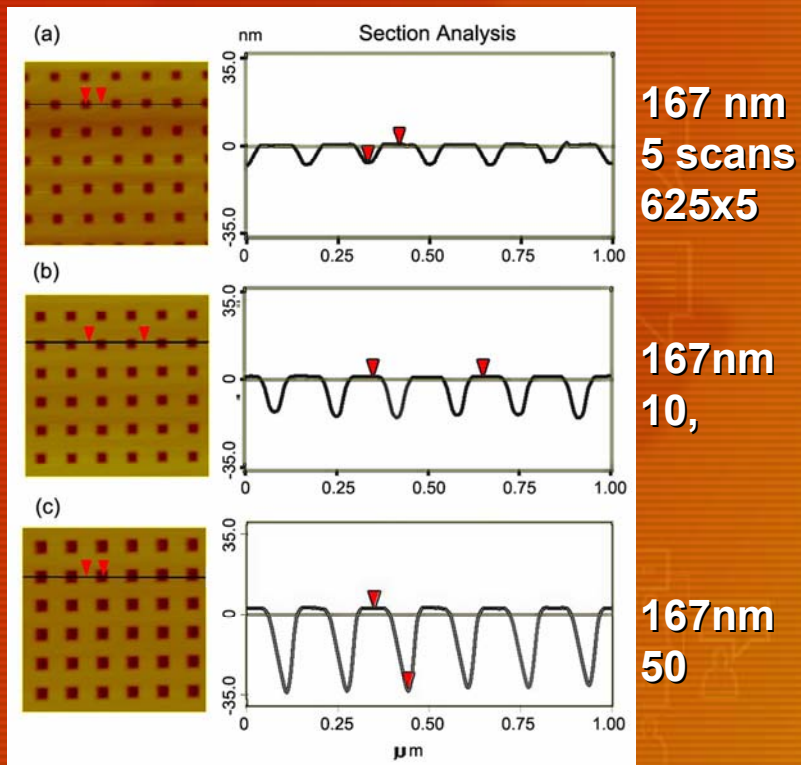
- **Comparison results**
 - Varying FIB dose
 - Varying spacing

Process conditions:

b) region

T = 700°C

Thickness: 7 Å



- All FIB patterns affected island growth
- Extra islands in (a) while there are still unfilled holes in (c)
 - volume of pits vs. amount of Cu_2O .



Results:

Patterned regions

- **Comparison results**
 - **Varying FIB dose**
 - **Varying spacing**

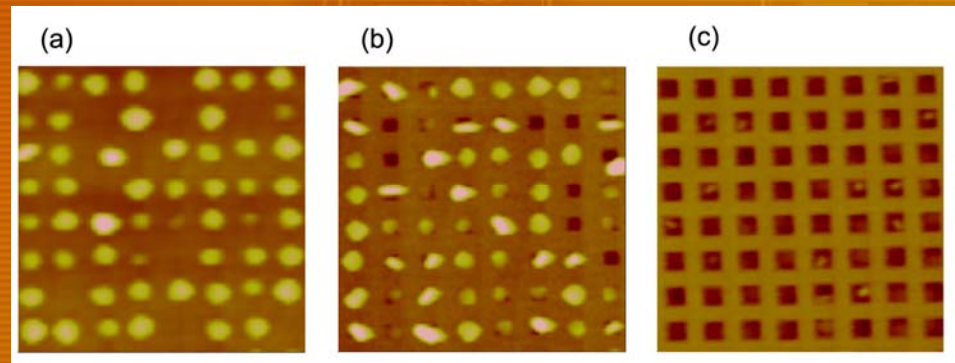
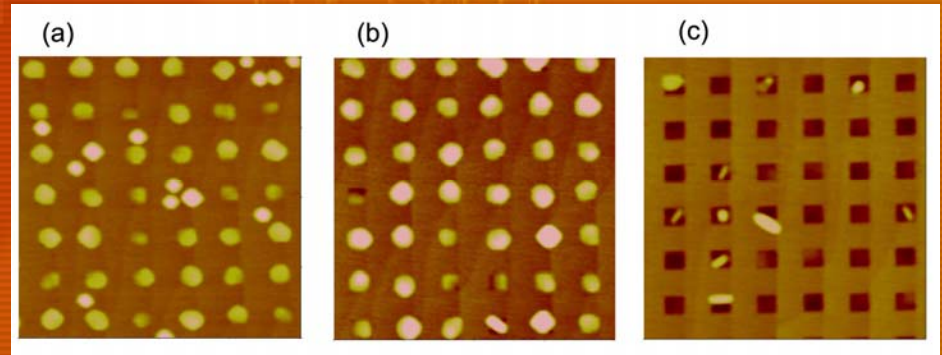
Process conditions:

b) region

T = 700°C

Thickness: 7 Å

167 nm spacing



130 nm spacing



Results:

Patterned regions

- **Comparison results**
 - **Varying FIB dose**
 - **Varying spacing**

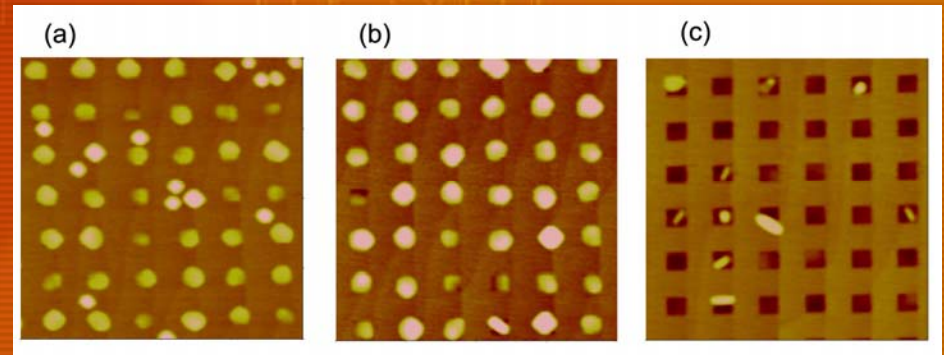
Process conditions:

b) region

T = 700°C

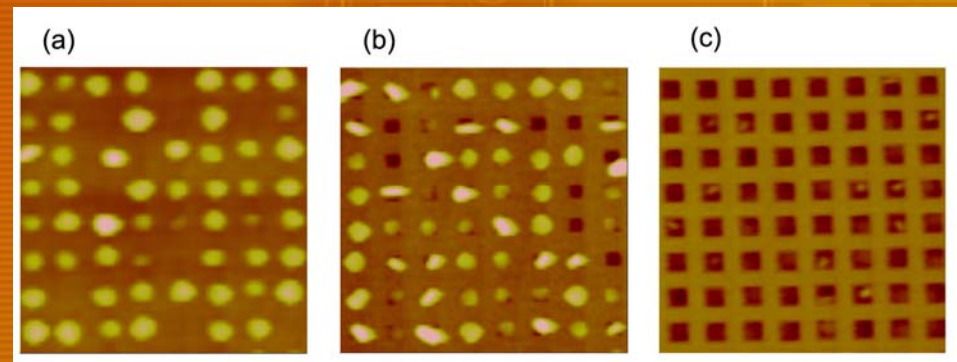
Thickness: 7 Å

167 nm spacing



Extra islands in 167 nm spacing pattern.

Unfilled FIB sites on 130 nm spacing pattern.



130 nm spacing



Results:

Patterned regions

- **Comparison results**
 - **Varying FIB dose**
 - **Varying spacing**

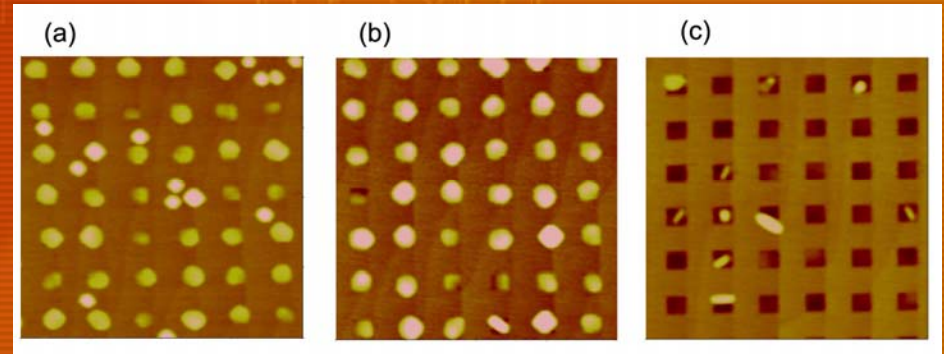
Process conditions:

b) region

T = 700°C

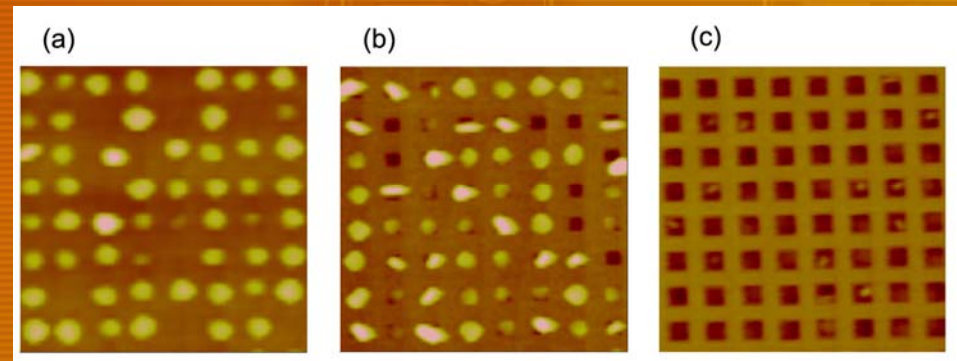
Thickness: 7 Å

167 nm spacing



One to one in 167 nm spacing pattern.

Unfilled FIB sites on 130 nm spacing pattern.



130 nm spacing



Results:

Patterned regions

- **Comparison results**
 - **Varying FIB dose**
 - **Varying spacing**
 - **Varying thickness**
 - **Varying temperature** ——— **More details are discussed in the poster.**

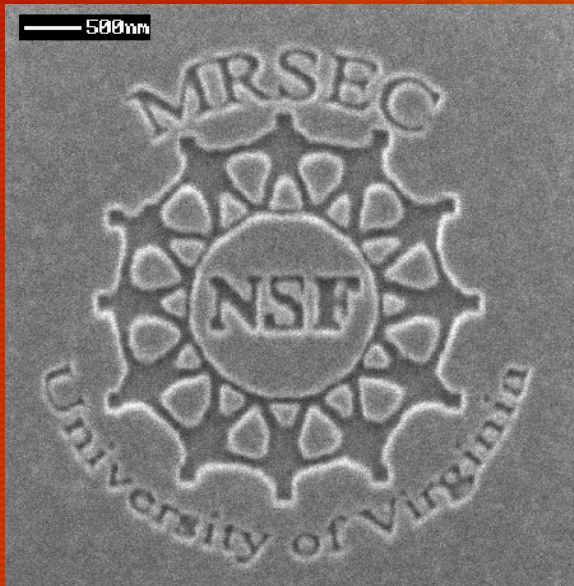


Discussions

- FIB patterning is a successful way to guide the growth of Cu_2O nanodots on SrTiO_3 (100) substrate.
 - Microscale 1:n; Nanoscale 1:1
 - Varying dosage to adjust the pit size
 - Varying thickness to fit different patterns
 - Varying patterns to fit certain density
- Possibility to extend this technique to other material systems
- Detailed growth mechanisms need to be further studied.
 - Ga^+ effect
 - Topography
 - Local stress/strain
 - Local chemistry



Acknowledgments:



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